PATENT APPLICATION

Docket Number 081468-0306527 Clent Reference: P-0382.010-US

THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Rethe Application of

ARNO JAN BLEEKER

Group Art Unit: 2881 285 |

Application No.: 10/715,116

Examiner: Unassigned Lalar

Filed: November 18, 2003

Confirmation No.: 3978

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

February 1, 2005

## **INFORMATION DISCLOSURE STATEMENT**

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
R	STREEFKERK et al. (081468-0309796)	10/850,451	05/21/2004	<ul> <li>✓ Specification</li> <li>✓ Drawings</li> <li>✓ Other: stamped receipt card</li> </ul>
327	MULKENS (081468-0310380)	10/890,389	07/14/2004	<ul><li>☒ Specification</li><li>☒ Drawings</li><li>☒ Other: stamped receipt card</li></ul>
PA	STREEFKERK et al. (081468-0309421)	10/844,575	05/13/2004	<ul><li>☑ Specification</li><li>☑ Drawings</li><li>☑ Other: stamped receipt card</li></ul>
Rt	SUWA et al. (Reissue Application of U.S. Patent No. 6,191,429 B1)	10/367,910	02/19/2003	Specification     Drawings     Other: stamped receipt card

<sup>\*</sup>The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re the Application of

Group Art Unit: 2851

Amo Jan BLEEKER
Application No.: 10/715,116

Examiner: Unassigned Fully

Filed: November 18, 2003

Confirmation No.: Unassigned

For: Lithographic Apparatus and Device Manufacturing Method

## INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P. O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
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Pr	Joeri LOF et al.	10/705,805	11/12/2003	<ul> <li>☑ Specification</li> <li>☑ Drawings</li> <li>☑ Other: stamped receipt card</li> </ul>
RA	Joeri LOF et al.	10/705,783	11/12/2003	
P	Helmar VAN SANTEN et al.	10/743,271	12/23/2003	⊠ Specification     ☑ Drawings     ☑ Other: stamped receipt card
7.3	Johannes C.H. MULKENS et al.	10/743,266	12/23/2003	<ul> <li>✓ Specification</li> <li>✓ Drawings</li> <li>✓ Other: stamped receipt card</li> </ul>
RX	Antonius T.A.M. DERKSEN et al.	10/705,785	11/12/2003	<ul><li>☒ Specification</li><li>☒ Drawings</li><li>☒ Other: stamped receipt card</li></ul>
W.	Klaus SIMON et al.	10/724,402	12/01/2003	<ul> <li>✓ Specification</li> <li>✓ Drawings</li> <li>✓ Other: stamped receipt card</li> </ul>
23	Joeri LOF et al.	10/705,816	11/12/2003	Specification     Drawings     Other: stamped receipt card
PA	Bob STREEFKERK et al.	10/719,683	11/24/2003	Specification     Drawings     Other: stamped receipt card
27	Joannes T. DESMIT et al.	10/705,804	11/12/2003	⊠ Specification     ☑ Drawings     ☑ Other: stamped receipt card

\*The Examiner's initials adjacept@ citation indicates he/she has considered the cited application relative to the subject application.

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